

Tool Code	PROCESS	EQUIPMENT	MANUFACTURER	MODEL	WAFER SIZE	VINTAGE
09357	TEST	SOC TESTER	ADVANTEST	T2000	-	2012
09359	TEST	SOC TESTER	ADVANTEST	T2000	-	2012
07855	EPI	EPI	Applied Materials	Centura Epi	200	1995
09311	ETCH	DRY ETCHER	Applied Materials	Centura II DPS+ Metal	150	2001
09382	CVD	PLASMA CVD	Applied Materials	PRODUCER	200	2000
09214	ION IMPLANT	IMPLANTER	Applied Materials	Quantum Leap	300	2007
07104	CVD	PLASMA CVD	ASM	Eagle10 TRIDENT	150	2007
06922	CVD	PLASMA CVD	ASM	Eagle10 TRIDENT	200	2003
09110	EPI	EPI	ASM	Epsilon-E2000	150	1998
09313	OTHERS	INSPECTION	CAMTEK	EAGLE-AP	150	2018
07888	PHOTOLITHO	STEPPER	Canon	FPA-3000EX6	200	2004
08293	RTP	RTA	Canon	HP-8800	200	2001
09244	PVD	SPUTTERING SYSTEM	CANON ANELVA	E-800S	-	-
09243	PVD	SPUTTERING SYSTEM	CANON ANELVA	E-800S	-	-
07426	PVD	SPUTTERING SYSTEM	CANON ANELVA	I-1060SV2 Plus1	200	2003
08273	PVD	SPUTTERING SYSTEM	CANON ANELVA	ILC-1080	200	2003
07837	DICING	DICER	DISCO	DFD6240	200	2004
07984	DICING	DICER	DISCO	DFD6340	200	-
09356	DICING	DICER	DISCO	DFD6361-2	300	2004
09212	PHOTOLITHO	COATER	EVG	EVG120	150/200	2015
07653	MARKING	Wafer Marker	GSI	MARK-EM	150	2002
07517	ETCH	ION MILLING	HITACHI	IML-6-1	150	1997
09259	ETCH	ION MILLING	Hitachi High-Tech	E-3500	-	2006
07960	METROLOGY	FIB	Hitachi High-Tech	FB-2100	-	2004
09265	METROLOGY	REVIEW SEM	Hitachi High-Tech	HD-2300	-	2004
09007	METROLOGY	REVIEW SEM	Hitachi High-Tech	HD-2300A	-	2007
07959	METROLOGY	REVIEW SEM	Hitachi High-Tech	HD2700B	-	2010
07852	METROLOGY	REVIEW SEM	Hitachi High-Tech	S-3400N	-	2010
09246	METROLOGY	REVIEW SEM	Hitachi High-Tech	SU1510	-	2009
09339	METROLOGY	REVIEW SEM	Hitachi High-Tech	SU3500	-	2018
07924	INSPECTION	VISUAL INSPECTION	INSPEC	LF2000	-	2005
07925	INSPECTION	VISUAL INSPECTION	INSPEC	LF2000	-	2005
07901	METROLOGY	FILM THICKNESS MEASUREMENT	JVS	JVX5200T	300	2005
07563	MARKING	LASER MARKER	KEYENCE	ML-Z9500/9510	-	2008
07878	METROLOGY	FILM THICKNESS MEASUREMENT	KLA-Tencor	OP3290	200	2004
07731	METROLOGY	STEP MEASURING SYSTEM	KLA-Tencor	P-11	100~200	2001
07929	METROLOGY	STEP MEASURING SYSTEM	KLA-Tencor	P-15	150~300	2004
09252	METROLOGY	WAFER PARTICLE COUNTER	KLA-Tencor	SP1-DLS	200	2005
09218	METROLOGY	WAFER PARTICLE COUNTER	KLA-Tencor	SP1-TBI	200/300	2001
07883	FURNACE	FURNACE_DIFFUSION	KOKUSAI ELECTRIC	DD-812V(N2 Anneal)	150	2007
07420	FURNACE	FURNACE_LP-CVD	KOKUSAI ELECTRIC	DJ-1206V-DF(ULT/SiO2)	300	2007
09061	CVD	CVD	Lam Research	CONCEPT ONE	125	1998
07706	METROLOGY	DUV DEFECT INSPECTION	Leica	INS3000	200	2001
07956	ETCH	OXIDE ETCHER	Mattson	ASPEN2-ICP-LE	200	1997
07992	ETCH	OXIDE ETCHER	Mattson	ASPEN2-RTA	200	1999
09052	WET	CLEANING SYSTEM	Mimasu	MSC-4000H	200	2005
09267	WET	CLEANING SYSTEM	Mimasu	MSE-3000Mi/MSP-2Mi	200	2006
08453	METROLOGY	FILM THICKNESS MEASUREMENT	Nanometrics	NanoSpec	150	1984
08422	METROLOGY	FILM THICKNESS MEASUREMENT	Nanometrics	NanoSpec	150	1985
08245	METROLOGY	FILM THICKNESS MEASUREMENT	Nanometrics	NanoSpec9200	200	2001
09323	PHOTOLITHO	STEPPER_i-Line	Nikon	NSR2205i11C	150	1997
09149	PHOTOLITHO	STEPPER_i-Line	Nikon	NSR-2205i11D	100	1995

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09326	PHOTOLITHO	STEPPER_i-Line	Nikon	NSR2205i12D	150	1999
07913	METROLOGY	MICROSCOPE	OLYMPUS	MX61L-F	-	2006
09053	ETCH	DRY ETCHER	Panasonic	E748SC	200	2006
07979	METROLOGY	AUTOMATIC VISUAL INSPECTION	RUDOLPH	AXi-935	200	-
09349	WET	POST CMP CLEANING SYSTEM	SCREEN	AS2000	200	2000
09352	WET	POST CMP CLEANING SYSTEM	SCREEN	AS2000	200	2000
09272	METROLOGY	FILM THICKNESS MEASUREMENT	SCREEN	VM-3210	150-300	2012
09208	ASHER	ASHER	SHIBAURA	μASH300	300	2004
09345	ION IMPLANT	IMPLANTER_HIGH CURRENT	SMIT	LEX	200	2007
09346	ION IMPLANT	IMPLANTER_HIGH CURRENT	SMIT	LEX3-M	300	2006
09344	ION IMPLANT	IMPLANTER_MEDIUM CURRENT	SMIT	MC3-CE	300	2005
09343	ION IMPLANT	IMPLANTER_MEDIUM CURRENT	SMIT	MC3-FOUP	300	2000
09330	ION IMPLANT	IMPLANTER_HIGH CURRENT	SMIT	NV-GSDⅢ-180	150	2003
09216	ION IMPLANT	IMPLANTER	SMIT	NV-GSDⅢ-90	125	2000
09348	ION IMPLANT	IMPLANTER_HIGH CURRENT	SMIT	NV-GSDⅢ-LE	200	2003
09331	ION IMPLANT	IMPLANTER_HIGH ENERGY	SMIT	NV-GSD-HE	150	2000
07990	ION IMPLANT	IMPLANTER_MEDIUM CURRENT	SMIT	NV-MC3	200	2001
09347	ION IMPLANT	IMPLANTER_HIGH CURRENT	SMIT	SHX/ⅢS	300	2014
09334	PHOTOLITHO	COATER&DEVELOPER	TEL	ACT8	200	1999
09099	PHOTOLITHO	COATER&DEVELOPER	TEL	Lithius i+	300	2005
07624	PHOTOLITHO	COATER	TEL	MARK-8	200	1996
09304	PHOTOLITHO	COATER	TEL	MARK-8	150	1992
07623	PHOTOLITHO	COATER&DEVELOPER	TEL	MARK-8	200	1998
09305	PHOTOLITHO	DEVELOPER	TEL	MARK-8	150	1993
07816	WET	WAFER SCRUBBER	TEL	SS-4	200	2003
09381	WET	WAFER SCRUBBER	TEL	SS-4	200	2000
08440	ETCH	OXIDE ETCHER	TEL	TE5000ATC	150	1992
07398	ETCH	OXIDE ETCHER	TEL	TE8500(S)ATC	150	1992
09210	ETCH	OXIDE ETCHER	TEL	Telius SCCM	300	2004
07571	ETCH	OXIDE ETCHER	TEL	Unity Me 85D	200	2003
07339	ETCH	OXIDE ETCHER	TEL	UnityII-855II	200	1996
07889	ETCH	OXIDE ETCHER	TEL	UnityIle-655PP	150	2000
09336	TEST	TESTER	TESEK	881TT/A	150	2007
09082	Vapor Deposition	Vapor Deposition	ULVAC	EBX-1000C	150	2006
09242	PVD	EVAPORATOR	ULVAC	ei-5	76.2/100	-
09083	Vapor Deposition	Vapor Deposition	ULVAC	EX-550-C10	150	1994
09241	ETCH	DRY ETCHER	ULVAC	NE-550EX	100	-
09200	PVD	SPUTTERING SYSTEM	ULVAC	SRH-420	200	2006
09100	PVD	SPUTTERING SYSTEM	ULVAC	SRH-530	100	2013
09379	IMPLANT	MEDIUM CURRENT ION IMPLANTER	VARIAN	E-500HP	200	1995
09380	IMPLANT	MEDIUM CURRENT ION IMPLANTER	VARIAN	VIIISION80	200	1996

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